

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	Ogata et al.
Appl. No.	:	10/588,866
Filed	:	August 9, 2006
For	:	POLYMER COMPOUND, PHOTORESIST COMPOSITION INCLUDING THE POLYMER COMPOUND, AND RESIST PATTERN FORMATION METHOD
Examiner	:	Walke, A.
Group Art Unit	:	1795

SUBMISSION WITH RCE

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the final Office Action mailed **November 30, 2009**, please consider the following amendments and remarks.

Amendments to the claims are reflected in the listing of claims begins on page 2 of this paper.

Remarks begin on page 4 of this paper.